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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority APPLICATION SERIAL NO. 08/984,730
Priority FILING DATE December 4, 1997
INVENTORSHIP D.G. Custer et al.
ASSIGNEE Micron Technology, Inc.
Priority GROUP ART UNIT 3723
Priority EXAMINER L. Wilson
ATTORNEY'S DOCKET NO. MI22-1172
TITLE: Polishing Systems, Methods of Polishing Substrates, and Methods of Preparing
Liquids for Semiconductor Fabrication Processes

Assistant Commissioner for Patents
Washington, D. C. 20231
Attention: Official Draftsman

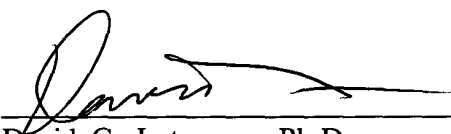
SUBSTITUTE DRAWING REQUEST

Please enter the enclosed substitute drawings in the above-referenced application in place of drawings originally filed. The content of the drawings are identical to those now on file in this application.

Acknowledgment of receipt of the formal drawings and their acceptance into the file is requested.

Respectfully submitted,

Date: 4/22/99

By: 
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Enclosures: 2 Sheets of Formal Drawings, Figs. 1-3.

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